CLAIMS

1. An Fe-Pt-BN-based sputtering target having a Vickers hardness of 150 or less, and comprising 20 mol% or more and less than 40 mol% of Pt and 25 mol% or more and 50 mol% or less of BN, with the balance being Fe and incidental impurities.

2. An Fe-Pt-BN-based sputtering target having a Vickers hardness of 150 or less, and comprising 20 mol% or more and less than 40 mol% of Pt, 10 mol% or more and less than 50 mol% of BN, and more than 0 mol% and 30 mol% or less of C, with the balance being Fe and incidental impurities, wherein a total content of BN and C is 25 mol% or more and 50 mol% or less.

3. The Fe-Pt-BN-based sputtering target according to Claim 1 or 2, further comprising one or more elements selected from Au, Ag, B, Cr, Cu, Ge, Ir, Ni, Pd, Rh, and Ru.

4. The Fe-Pt-BN-based sputtering target according to Claim 3, wherein a total content of one or more elements selected from Au, Ag, B, Cr, Cu, Ge, Ir, Ni, Pd, Rh, and Ru is 15 mol% or less.

5. The Fe-Pt-BN-based sputtering target according to any one of Claims 1 to 4, having a relative density of 90% or more.

6. A method of producing the Fe-Pt-BN-based sputtering target according to Claim 1, comprising

feeding Fe powder, Pt powder, and BN powder into a stirred media mill and mixing at 100 rpm or more and 300 rpm or less for 1 hour or more and 6 hours or less to obtain a raw material powder mixture; and

sintering the raw material powder mixture, wherein

hot isostatic pressing (HIP) is not performed.

7. A method of producing the Fe-Pt-BN-based sputtering target according to Claim 2, comprising

feeding Fe powder, Pt powder, BN powder, and C powder into a stirred media mill and mixing at 100 rpm or more and 300 rpm or less for 1 hour or more and 6 hours or less to obtain a raw material powder mixture; and

sintering the raw material powder mixture, wherein

hot isostatic pressing (HIP) is not performed.